



IN THE CLAIMS

Claims 2-3 are pending in this application. Please amend claim 3 as follows:

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1. (Canceled)
2. (Previously Presented) A method for purifying semiconductor nanoparticles, comprising the steps of:
 - modifying semiconductor nanoparticles with oil-soluble materials for surface modification;
 - converting the oil-soluble materials for surface modification into water-soluble materials for surface modification at the interface between an organic solvent and water;
 - shifting the semiconductor nanoparticles from an organic phase to an aqueous phase by the conversion; and then
 - subjecting the semiconductor nanoparticles, the surfaces of which have been modified with the water-soluble materials for surface modification, to size-selective photoetching, wherein the surface of the semiconductor nanoparticles is dissolved and peeled by the size-selective photoetching, and particle sizes of the semiconductor nanoparticles are regulated and the semiconductor nanoparticles are monodispersed by the dissolution.
3. (Currently Amended) A method for purifying semiconductor nanoparticles, comprising the steps of:
 - modifying semiconductor nanoparticles with oil-soluble materials for surface modification;
 - converting the oil-soluble materials for surface modification into water-soluble materials for surface modification at the interface between an organic solvent and water;
 - shifting the semiconductor nanoparticles from an organic phase to an aqueous phase by the conversion; and then
 - subjecting the semiconductor nanoparticles, the surfaces of which have been modified with the water-soluble materials for surface modification, to size-selective photoetching, whereby the dissolution caused thereby is utilized to peel the surface